

U.S. Department of Commerce, Patent and Trademark Office						Atty Docket No.	Serial No.
						M-11706 US	09/902,931
INFORMATION DISCLOSURE STATEMENT BY APPLICANT						Applicant(s)	
(Use several sheets if necessary)						Martin, Kirk	
						Filing Date	Group
						July 10, 2001	
U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
Foreign Patent Documents							
		Document	Date	Country	Class	Subclass	Translation
	AB						Yes
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
LV	AC	Weavers, Barry A., "Chemical Thinning of Silicon for Emission Microscopy Using Multi Etch--An Introduction," Nisene Technology Group, Inc., B&G International Division, August 2000, pp. 1-6.					
	AD	Hypervision, "HYPERVISION's PTF1 Portable Test Floor Emission Microscope," Hypervision Inc., 2000, pp. 1-8.					
	AE	Hypervision, "Sensor and Optics Technology: BEAMS and Mercad Telluride (MCT)", Hypervision Inc., 2000, pp. 1-8.					
	AF	Hypervision, "Chip UnZip Backside Preparation Tool," Hypervision Inc., 2000, pp. 1-4.					
	AG	Hypervision, "Chip UnZip: Low Stress Backside Semiconductor Preparation," Hypervision, 1998, pp. 1-4.					
	AH	Adams, Tom, "Backside Emission Microscopy of Wafers," <i>News and Analysis @Semiconductor Online</i> , February 28, 2000, pp. 1-3.					
	AI	Adams, Tom, "Bringing the Emission Microscope to the Test Floor," <i>News and Analysis @Semiconductor Online</i> , July 1, 1999, pp. 1-4.					
	AJ	Hypervision, "BEAMS™ (Backside Emission Analysis Microscope System)", Hypervision Inc., 1998, p.1.					
	AK	Clark, Scott, MSCE, "Etching Silicon Dioxide with Aqueous HF Solutions," <i>Silicon Dioxide Etch</i> , Bold Technologies, January 29, 2001, pp. 1-5.					
	AL	Bold Technologies, "Manual Equipment", Bold Technologies, Inc., 1998-2000, pp. 1-3.					
LV	AM	Nisene Technology Group, "MultiEtch System," Nisene Technology Group, Inc., July 12, 2000, pp. 1-4.					
Examiner		LAN VINH		Date Considered		2/3/2003	
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.							